Kunio Okimura

List of Publications by Year
in descending order

50	823	516710 16	501196 28
papers	citations	h-index	g-index

50	50	50	942
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	In situ x-ray diffraction studies on epitaxial VO2 films grown on c-Al2O3 during thermally induced insulator-metal transition. Journal of Applied Physics, 2010, 107, 063503.	2.5	58
2	Temperature-dependent Raman and ultraviolet photoelectron spectroscopy studies on phase transition behavior of VO2 films with M1 and M2 phases. Journal of Applied Physics, 2014, 115, .	2.5	56
3	Stress-induced VO2 films with M2 monoclinic phase stable at room temperature grown by inductively coupled plasma-assisted reactive sputtering. Journal of Applied Physics, 2012, 111, .	2.5	51
4	Changes in Lattice Parameters of VO₂ Films Grown on c-Plane Al₂O₃ Substrates across Metalâ€“Insulator Transition. Japanese Journal of Applied Physics, 2009, 48, 045504.	1.5	46
5	Electric-Field-Induced Multistep Resistance Switching in Planar VO₂/c-Al₂O₃ Structure. Japanese Journal of Applied Physics, 2009, 48, 065003.	1.5	45
6	Radio frequency substrate biasing effects on the insulator-metal transition behavior of reactively sputtered VO2 films on sapphire (001). Journal of Applied Physics, 2015, 117, .	2.5	43
7	Self-oscillation up to 9â€‰MHz based on voltage triggered switching in VO2/TiN point contact junctions. Journal of Applied Physics, 2015, 117, .	2.5	36
8	Dynamically Babinet-invertible metasurface: a capacitive-inductive reconfigurable filter for terahertz waves using vanadium-dioxide metal-insulator transition. Optics Express, 2016, 24, 4405.	3.4	35
9	Preparation of VO2Films with Metal-Insulator Transition on Sapphire and Silicon Substrates by Inductively Coupled Plasma-Assisted Sputtering. Japanese Journal of Applied Physics, 2005, 44, L1150-L1153.	1.5	34
10	Pulsed laser-deposited VO2 thin films on Pt layers. Journal of Applied Physics, 2013, 113, .	2.5	34
11	Polarized Raman scattering of large crystalline domains in VO2 films on sapphire. Vibrational Spectroscopy, 2015, 80, 79-85.	2.2	32
12	Photo-induced lattice softening of excited-state VO2. Applied Physics Letters, 2011, 99, .	3.3	28
13	Anisotropic Babinet-Invertible Metasurfaces to Realize Transmission-Reflection Switching for Orthogonal Polarizations of Light. Physical Review Applied, 2016, 6, .	3.8	27
14	Impact of thermal expansion of substrates on phase transition temperature of VO2 films. Journal of Applied Physics, 2014, 116, 123510.	2.5	25
15	Reconfigurable Terahertz Quarter-Wave Plate for Helicity Switching Based on Babinet Inversion of an Anisotropic Checkerboard Metasurface. Physical Review Applied, 2019, 11, .	3.8	22
16	Infrared-light switching in highly oriented VO2 films on ZnO-buffered glasses with controlled phase transition temperatures. Solar Energy Materials and Solar Cells, 2019, 191, 9-14.	6.2	17
17	Titanium atom densities in reactive rf magnetron sputtering for TiO2 deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 1-6.	2.1	15
18	Appearance of large crystalline domains in VO2 films grown on sapphire (001) and their phase transition characteristics. Journal of Applied Physics, 2015, 117, .	2.5	15

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19	X-ray Diffraction Study of Electric Field-Induced Metalâ€“Insulator Transition of Vanadium Dioxide Film on Sapphire Substrate. Japanese Journal of Applied Physics, 2006, 45, 9200-9202.	1.5	14
20	Low-temperature growth of VO2 films on transparent ZnO/glass and Al-doped ZnO/glass and their optical transition properties. Thin Solid Films, 2018, 651, 91-96.	1.8	14
21	Broadband operation of active terahertz quarter-wave plate achieved with vanadium-dioxide-based metasurface switchable by current injection. Applied Physics Letters, 2020, 117, .	3.3	14
22	Performance of inductively coupled plasma assisted sputtering with internal coil for ferromagnetic CoCrTa film deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 39-45.	2.1	13
23	Phase selective growth and characterization of vanadium dioxide films on silicon substrates. Journal of Applied Physics, 2013, 113, 163503.	2.5	13
24	Growth of VO2 films with metal-insulator transition on silicon substrates in inductively coupled plasma-assisted sputtering. Thin Solid Films, 2007, 515, 4992-4995.	1.8	12
25	Effects of energetic substrate-incident ions on the growth of crystalline vanadium dioxide films in inductively coupled plasma-assisted sputtering. Japanese Journal of Applied Physics, 2014, 53, 035802.	1.5	12
26	Large modification in insulator-metal transition of VO2 films grown on Al2O3 (001) by high energy ion irradiation in biased reactive sputtering. Journal of Applied Physics, 2016, 119, 055308.	2.5	12
27	Coupled oscillations of VO2-based layered structures: Experiment and simulation approach. Journal of Applied Physics, 2020, 127, .	2.5	12
28	Effect of conductive TiN buffer layer on the growth of stoichiometric VO2 films and the out-of-plane insulatorâ€“metal transition properties. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, .	2.1	11
29	Ionic densities and ionization fractions of sputtered titanium in radio frequency magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2003, 21, 988-993.	2.1	9
30	Epitaxial Growth of Rutile TiO2Films on MgO Substrate in Inductively Coupled Plasma-Assisted Sputtering. Japanese Journal of Applied Physics, 2004, 43, L655-L658.	1.5	9
31	Dynamic Quarterâ€Wave Metasurface for Efficient Helicity Inversion of Polarization Beyond the Singleâ€Layer Conversion Limit. Advanced Optical Materials, 2022, 10, 2101615.	7.3	9
32	Oriented growth of VO2(B) thin films on Mo foils by reactive sputtering for lithium ion batteries. Thin Solid Films, 2016, 616, 95-100.	1.8	8
33	Growth of Highly Oriented CoCrTa films by Inductively Coupled Plasma-Assisted Sputtering. Japanese Journal of Applied Physics, 2003, 42, 3641-3647.	1.5	7
34	Low-temperature oriented growth of vanadium dioxide films on CoCrTa metal template on Si and vertical metalâ€“insulator transition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2012, 30, .	2.1	7
35	Persistent M2 phase in strongly strained (011)-oriented grains in VO2 films grown on sapphire (001) in reactive sputtering. Journal of Applied Physics, 2019, 125, .	2.5	7
36	Approaching ultrathin VO2 films on sapphire (001) substrates by biased reactive sputtering: Characteristic morphology and its effect on the infrared-light switching. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	2.1	5

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37	Dynamic inversion of planar-chiral response of terahertz metasurface based on critical transition of checkerboard structures. Nanophotonics, 2022, 11, 2057-2064.	6.0	4
38	Simultaneous realization of infrared-light switching and high visible-light transmittance in extremely thin VO2 films grown on ZnO-nanorods buffered glasses. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	2.1	3
39	EFFECT OF LIGHT IRRADIATION ON ELECTRIC-FIELD-INDUCED RESISTANCE SWITCHING PHENOMENON IN PLANAR VO2/c-Al2O3 STRUCTURE. International Journal of Nanoscience, 2009, 08, 147-150.	0.7	2
40	Recrystallization of VO2 films into (011)-oriented micrometer-sized grains on Al2O3 (001) in biased reactive sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 061508.	2.1	2
41	Electrochemical Probing of H2O2 Using TiO2-ZrO2-HfO2 Modified Glassy Carbon Electrode: A Promoted Sacrificial Behavior of Hf4+ ions. Water, Air, and Soil Pollution, 2021, 232, 1.	2.4	2
42	Activities of Sputtering and Plasma Process (SP) Division. Vacuum and Surface Science, 2018, 61, 88-90.	0.1	1
43	Stress-Induced In Situ Modification of Transition Temperature in VO2 Films Capped by Chalcogenide. Materials, 2020, 13, 5541.	2.9	1
44	VO2 films on flexible thin polyimide films: Fabrication and characterization of electrical and optical properties in insulator-metal transition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	2.1	1
45	Plasma cleaning of Si surfaces for TiO2 film deposition. Electronics and Communications in Japan, 2000, 83, 9-13.	0.2	0
46	Measurement of Ti Atom Densities Using Atomic Absorption Method in Ti-O2 Magnetron Sputtering.. Shinku/Journal of the Vacuum Society of Japan, 2000, 43, 197-200.	0.2	0
47	Investigation of Thin Film Deposited by Photo Enhanced Chemical Vapor Deposition with Vacuum Ultra Violet as a Light Source using Tetraethoxysilane.. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 1018-1022.	0.2	0
48	Measurement of Ti Atom Densities Against Discharge Parameters in Ti-O2 Magnetron Sputtering.. Shinku/Journal of the Vacuum Society of Japan, 2001, 44, 314-317.	0.2	0
49	Measurements of Ti Atom Density and Ti ion Density in Inductively Coupled Plasma Enhanced Magnetron Sputtering. Shinku/Journal of the Vacuum Society of Japan, 2003, 46, 462-465.	0.2	0
50	Optical Absorption Measurements of Sputtered Ti Ion Density and Discussion of Ionization Mechanisms in Inductively Coupled Plasma-Assisted DC Sputtering. Journal of Plasma and Fusion Research, 2004, 80, 619-625.	0.4	0